

**REMARKS**

At the outset, the Examiner is thanked for the thorough review and consideration of the subject application. Further, the Examiner is thanked for the courtesies extended during a telephone interview on October 14, 2003. During the telephone interview, in which the Examiner and Applicants' representative Kurt M. Eaton participated, Kwon et al. (U.S. Pat. No. 6,399,165), as applied in the Final Office Action dated May 15, 2003 and as discussed in the Advisory Action dated October 7, 2003, was discussed.

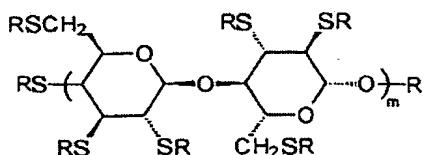
By the present amendment, Applicants hereby amend claim 1, cancel claims 5 and 6, and respectfully submit no new matter has been entered.

In the Final Office Action, the Examiner rejected claims 1-6 under 35 U.S.C. § 102(e) as being anticipated by Kwon et al.; and rejected claims 1-6 under the judicially created doctrine of double patenting over claims 1-34 of Kwon et al.

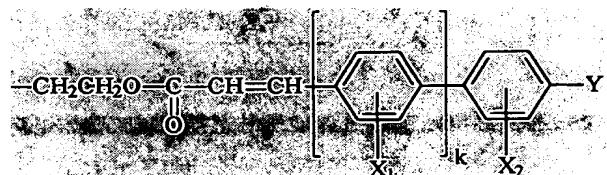
Applicants submit that the rejections set forth in the Final Office Action are moot in view of the amendments set forth herein. Reconsideration of the claims is respectfully requested in view of the foregoing amendments to the claims and in view of the following remarks.

The rejections of claims 1-6 under 35 U.S.C. § 102(e) as being anticipated by Kwon et al., and under the judicially created doctrine of double patenting over claims 1-34 of Kwon et al., are respectfully traversed and reconsideration is requested.

Claim 1 is allowable over the cited references in that claim 1 recites a combination of elements including, for example “a first alignment layer on the first substrate, wherein the first alignment layer includes



where the spacer S is selected from the group consisting of oxygen, sulfur, NH, OC<sub>h</sub>H<sub>2h</sub>, and OC<sub>h</sub>H<sub>2h</sub>O, where h = 1~5 and m = 10~10,000, and the functional group R includes a material selected from consisting of OH, SH, and



, wherein X<sub>1</sub> and X<sub>2</sub> are each selected from the group consisting of hydrogen, fluorine, chlorine, CN, NO<sub>2</sub>, CH<sub>3</sub>, OCH<sub>3</sub>, CF<sub>3</sub>, and OCF<sub>3</sub>; k is 0 to 1; Y is selected from the group consisting of hydrogen, fluorine, chlorine, CN, NO<sub>2</sub>, CF<sub>3</sub>, OCF<sub>3</sub>, C<sub>n</sub>H<sub>2n+1</sub>, OC<sub>n</sub>H<sub>2n+1</sub>, C<sub>n</sub>H<sub>2n+1-x</sub>F<sub>x</sub>, and OC<sub>n</sub>H<sub>2n+1-x</sub>F<sub>x</sub> (n = 1~10, x = 1~2n+1)..." None of the cited references, including Kwon et al., singly or in combination, teaches or suggests at least this feature of the claimed invention. Accordingly, Applicants respectfully submit that claims 2-6 which depend from claim 1 are also allowable over the cited references.

Should the Examiner deem that a telephone conference would further the prosecution of this application, the Examiner is invited to call the undersigned attorney at (202) 496-7500.

Application No.: 09/534,723  
Group Art Unit: 1772

Docket No.: 8733.229.00  
Page 16 of 16

The Director is hereby authorized to charge any deficiency in the fees filed, asserted to be filed or which should have been filed herewith (or with any paper hereafter filed in this application by this firm) to our Deposit Account No. 50-0911, under Order No. 8733.229.00-US. A duplicate copy of this paper is enclosed.

Respectfully submitted,

McKENNA LONG & ALDRIDGE LLP

Date: November 14, 2003

By 

Kurt M. Eaton  
Registration No. 51,640

1900 K Street, N.W.  
Washington, D.C. 20006  
Telephone No.: (202) 496-7500  
Facsimile No.: (202) 496-7756